

The impact of film thickness on the structural, optical, and electrical characteristics of SnO₂ thin films produced using the thermal spraying method

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Abstract :

The objective of this study is to investigate the augmentation of the layer count in SnO₂ thin films. Films were created on glass substrates using thermal spraying with different numbers of sputters (10, 20, 30, 40, and 50). Based on the X-ray diffraction (XRD) pattern, the films show a tetracrySTALLINE structure, with the (110) direction displayed at the highest intensity. The data show the generation of samples with crystal diameters ranging from 60 to 120 nm. Through the use of FESEM imaging, it is shown that the nanoparticles underwent a shape transformation, moving from a spherical shape to an agglomerate-like structure in response to changes in thickness, and this resulted in an increase in optical absorption and a decrease in the optical band gap width from 3.93 eV to 3.83 eV. By manipulating the bias voltage and light intensity, it was shown that the photocurrent showed exponential growth, indicating a Schottky-like behavior in the current-voltage (IV) characteristics.

Keywords: SnO₂, Thin film, spraying method, characteristics of SnO₂, film thickness.

دراسة تأثير زيادة طبقات غشاء SnO₂ على الخصائص التركيبية والضوئية والكهربائية المرسبة بطريقة الرش الكيميائي الحراري

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مستخلص:

تدرس هذه الورقة البحثية تأثير زيادة عدد الطبقات أغشية أو أكسيد القصدير ، رسبت الأغشية على قواعد زجاجية باستخدام تقنية الرش الكيميائي الحراري، مع ترسيب عدد من الطبقات كل طبقة بعدد رشات مختلفة تبدأ (10، 20، 30، 40، 50) رشة على التوالي. وفقاً لشكل حيود الأشعة السينية (XRD)، تظهر الأغشية بنية رباعية البلورات، حيث يمتلك الاتجاه (110) وهو يعتبر الاتجاهية المفضلة لنمو للأغشية والاعلى شدة. تبين صور و نتائج FESEM عينات بأقطار بلورية تتراوح من 60 إلى 120 نانومتر، لوحظ أن الجسيمات النانوية تخضع لتحويلات في الشكل مع تغيرات عند زيادة عدد الطبقات، من الشكل الكروي إلى الهيكل الكروي المتكامل العشوائي ، هذه الزيادة في سمك الغشاء الرقيق تؤدي إلى زيادة امتصاص الضوء وتقليل الفجوة الضوئية ، حيث يتراوح عرض فجوة الطاقة البصرية بين 3.93eV إلى 3.83eV. من خلال نتائج جهد الانحياز الامامي والعكسي للتيار- فولتية في حالة الظلام و الضوء، أظهرت النتائج أن التيار الكهروضوئي ينمو بشكل أسي للانحياز مما يشير إلى أن خصائص تيار-فولتية تُظهر سلوكاً مشابهاً لسلوك شوتكي.

الكلمات المفتاحية: SnO₂، الغشاء الرقيق، طرق الترسيب الكيميائي، خصائص SnO₂، سمك الغشاء.

1. Introduction

Nano-sized semiconductor metal oxides (MOs) have received much attention due to their interesting electrical and optical properties [1],[2]. Tin dioxide (SnO₂), also known as stannous oxide, is a transition metal oxide that has been widely studied and used. Tin oxide, or tin dioxide (SnO₂), has a remarkable straight bandgap, making it highly transparent in the visible spectrum. In addition, this compound has chemical and mechanical stability, is environmentally friendly, and has a low level of electrical resistance [3]-[6]. Therefore, SnO₂ is used in solar cells, gas sensors, and biosensors [7]-[9]. SnO₂, one of the prominent metal oxide semiconductors, is widely used as a gas-sensing material due to its very favorable surfaces for gas adsorption, both physically and chemically [10]. These sensors are very important and play a vital role in the fields of industrial processing, environmental protection, and medical treatment. However, there are additional hurdles that need to be resolved to effectively employ these sensors in different applications. Current efforts are focused on

conducting comprehensive research to improve the selectivity, sensitivity, and stability of sensors. Current research is focused on several areas, including the integration of different additives [11], the production of multilayer films [12], the construction of an electronic nose using network recognition algorithms [13], and the application of innovative techniques for the production of sensor films [14]. Recently, there has been an increasing focus on SnO₂-based thin-film sensors composed of nanoparticles and nanostructures. The reason for this is that these films show exceptional characteristics, such as small size, high sensitivity, strong stability, fast reaction, and fast recovery. Historically, several conventional techniques have been used to manufacture gas-sensing films. Techniques mentioned include thermochemical spraying, screen printing, physical and chemical vapor deposition (PVD and CVP), dip coating, and gel-based spin coating [15]. However, these methods fail to meet all the criteria necessary to create sensors of exceptional quality. Developing electronics presents a great difficulty in terms of depositing films with complex designs or integrating many gas

detection films on a single chip. This approach has great potential in transferring trace amounts of material and creating pre-defined patterns, giving it an advantage over traditional deposition methods [16]. Spray pyrolysis is a promising technology for material production. Thermal chemical spraying technology is widely used and frequently used. Spray pyrolysis has attracted great interest in the world of materials and device preparation due to its many benefits. The benefits of this technology include the ability to process materials without the need for a vacuum, the ability to perform high-throughput combinatorial chemistry, the ability to process materials at low temperatures, cost-effectiveness, and minimal material waste [14]-[17]. The application of thermal breakdown as a means of producing various functional films, such as thin-film transistors (TFT), has been studied [18]. The research aims to determine the extent of the effect of increasing the number of layers on the membranes and to know the electrical behavior of these membranes.

2. Experimental methods

The fabrication was performed for

thin films of tin dioxide on a glass substrate. To begin, glass slides were cleaned ultrasonically for 10 min using a mixture of distilled water and ethanol. Pure SnO₂ solution was prepared using aqueous tin chloride SnCl₄·2H₂O has the following specifications: molecular weight = 225.63 g/mol, purity = 99.9%, color = white crystals that dissolve quickly in deionized water. Aqueous tin chloride was prepared with molarity (0.1 mol/L) and volume (100 mL). Amounts of 2.4 grams of aqueous tin chloride were dissolved to the desired concentration in 100 mL of nonionic water. Then mix the solution using a magnetic mixer for (5-10 minutes). After dissolving the entire substance, the solution is then placed in the tank of the spray device, and the solution is sprayed onto the heated base at a temperature of 300 degrees Celsius for several different sprays (10, 30, 50). This temperature was obtained experimentally in batches over specific time periods. There was a spraying period of 15 seconds and a pause of 60 seconds, to ensure that the temperature of the substrates after spraying returned to its temperature before spraying, which decreased

due to the cooling resulting from the flow spraying. When the deposition process in the previous steps is completed, the glass substrates are then left on the surface of the heater after turning it off until they cool without trying to lift them, to avoid breaking the film when trying to lift it suddenly from the surface of the heater as a result of the temperature difference (rapid cooling).

3. Results and discussion

3.1 Structure and Morphological Properties

Figure 1 displays the X-ray diffraction (XRD) patterns of tin dioxide films that were deposited to glass substrates using different numbers of sprays. The generated films showed a polycrystalline structure and a tetragonal phase, with a diffraction angle of 26.40° and a preferred direction of 110. The diffraction angles of two additional peaks, (101) and (211), were determined to be 33.21° and 51.41°, respectively, and these angles fluctuated slightly. When the number of deposition layers increases. This finding is substantiated by data provided on JCPDS Card No. 00-024-1342 and 01-077-0452. As shown in the figure, three crystalline

directions (110), (101), and (211) grew, and the direction (110) was dominant at different numbers of sprays. It is noted that the peaks were low in intensity, not moderate, and regular in shape. The reason is the lack of the number of deposition or crystalline irregularity, which causes some dislocations in the crystal and the breaking of atomic bonds. As the number of layers rises, the magnitude of the peaks intensifies. These findings align with previous studies conducted by other researchers [19]-[21]. The crystal size can be determined using the Debye-Scherrer equation, which is expressed as

$$D = k\lambda\beta\cos\theta \text{-----(1)}$$

The shape factor, represented by the variable k, has a value of 0.94 in this specific context. The symbol β represents the full width at half maximum, while the diffraction peak angle is called θ. The X-ray source emits radiation with a wavelength of 0.15405 nm. It was found that the diameters of the crystals ranged from 60 to 120 nanometers. The data shown in Table 1 demonstrates that there was a noticeable rise in the average crystal size as the number of layers grew from 10 to 50. The number of layers has a direct

impact on both the crystal structure and the size of the nanoparticles. The data indicates a positive correlation between the number of layers and the average crystal size. This implies that as the number of layers, or the amount of material deposited, grows, the average

crystal size also increases. The number of layers directly affects all crystal properties. In line with other research [22], [23], our research indicates that there was growth in crystal size when the number of layers was raised from 10 - 50.

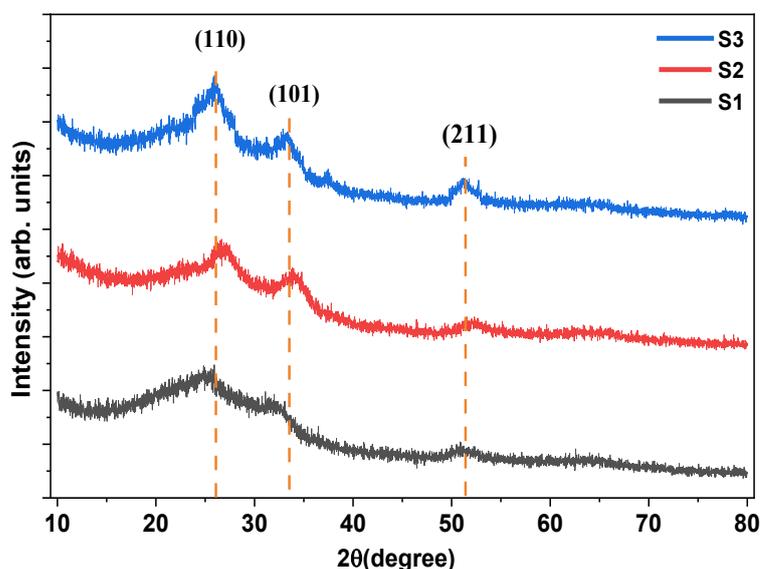


Figure 1: XRD patterns of SnO₂- S1(10-) :Sprinkles), S2(30-) :Sprinkles), and S3(50-) :Sprinkles)

Table 1: Characterize the structural properties of the SnO₂ thin films formed at various Sprinkles values.: S1 (10-Sprinkles), S2 (30-Sprinkles), and S3 (40-Sprinkles).

Sample	Pos. [°2Th.]	Postcard. [°2Th.]	FWHM [°2Th.]	d-spacing [Å]	d-spacing card [Å]	Rel. Int. [%]	D(nm)	(hkl)
S1	26.4011	26.1884	0.0708	3.14262	3.4	18.88	115.68	110
	33.2119	33.5357	0.0708	2.29753	2.67	14.92	29.36	101
	51.4761	51.5943	0.1417	1.7753	1.77	22.14	62.46	211
S3	26.1577	26.1884	0.2362	3.06277	3.4	53.41	34.66	110
	33.285	33.5357	0.0945	2.61557	2.67	13.59	88.07	101
	51.4179	51.5943	0.144	1.97964	1.77	21.16	61.45	211
S5	26.8436	26.1884	0.3779	3.32132	3.4	28.12	21.69	110
	32.9965	33.5357	0.0708	2.00758	2.67	8	117.46	101
	51.8868	51.5943	0.0708	1.82807	1.77	17.02	125.24	211

3.2. Morphology characterization of SnO₂

Figure 2 depicts photographs of tin dioxide samples created by thermal spraying methods. Images were acquired using FESEM, which stands for field emission scanning electron microscopy. The number of sprays (film layers) has a significant influence on both the size and structure of SnO₂ nanoparticles, making it a critical factor in their formation. The agglomerated particles showed several distinct shapes. Particles with an average diameter of 30 nm showed a spherical shape and after 10 sprays, the particle size expanded to 60 nm and turned into an oval shape. When the number of sprays increased to 30, the particle size showed a significant decrease to 26 nm at the number of sprays 50, and the structure took the appearance of spheres. Small nanoparticles. Increasing the number of sprays led to the agglomeration process, as shown in SEM images Figure 2: S3 [24].

Figure 3 displays the cross-sectional FESEM picture. The SnO₂ films were found to have a thickness of around 72 nm. As the number of spits rises, the material's thickness increases to 174 nm at 30 spits and continues to increase. Spit 30 times. The wavelength is around 1350 nm when using 50 sprays.

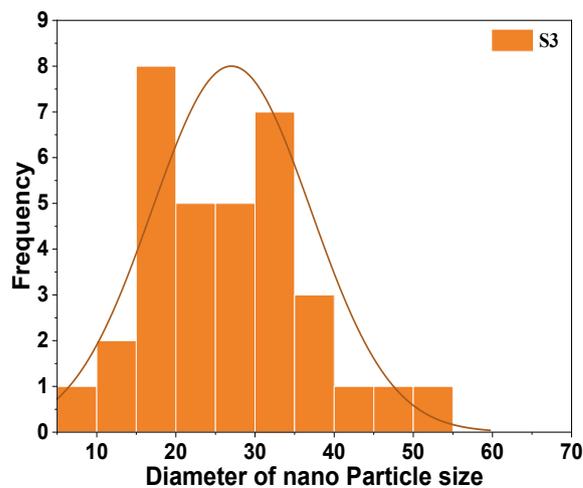
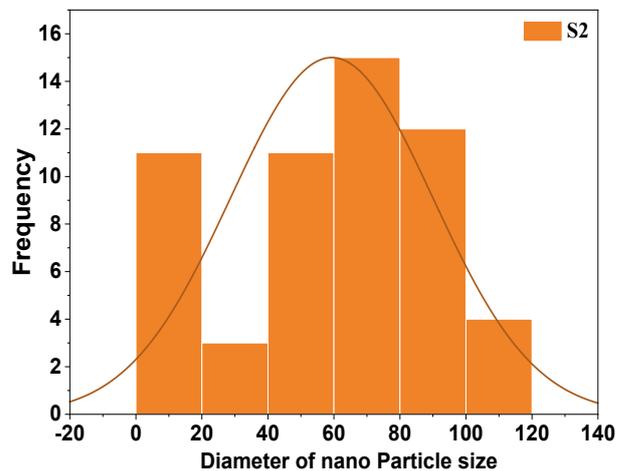
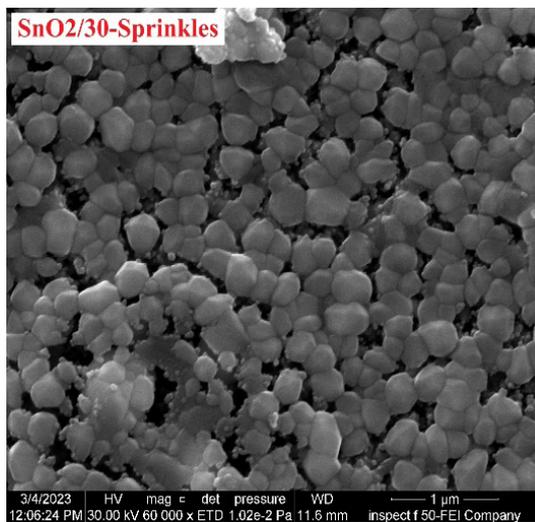
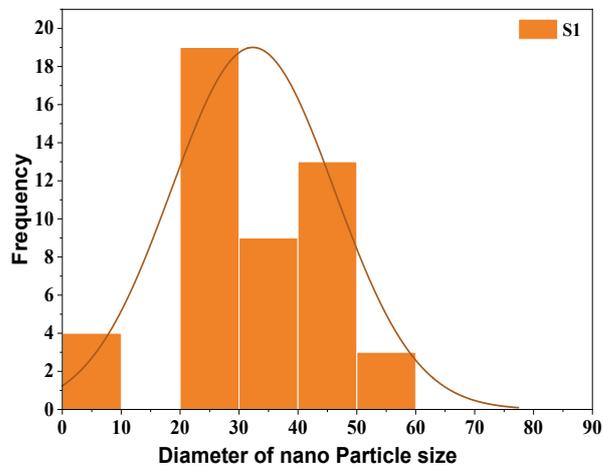
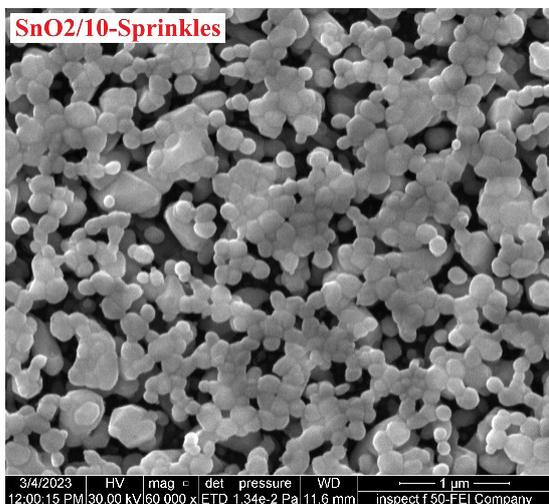


Figure 2: FESEM images of SnO₂ at S110-) :Sprinkles), S230-) :Sprinkles), and S350-) :Sprinkles).

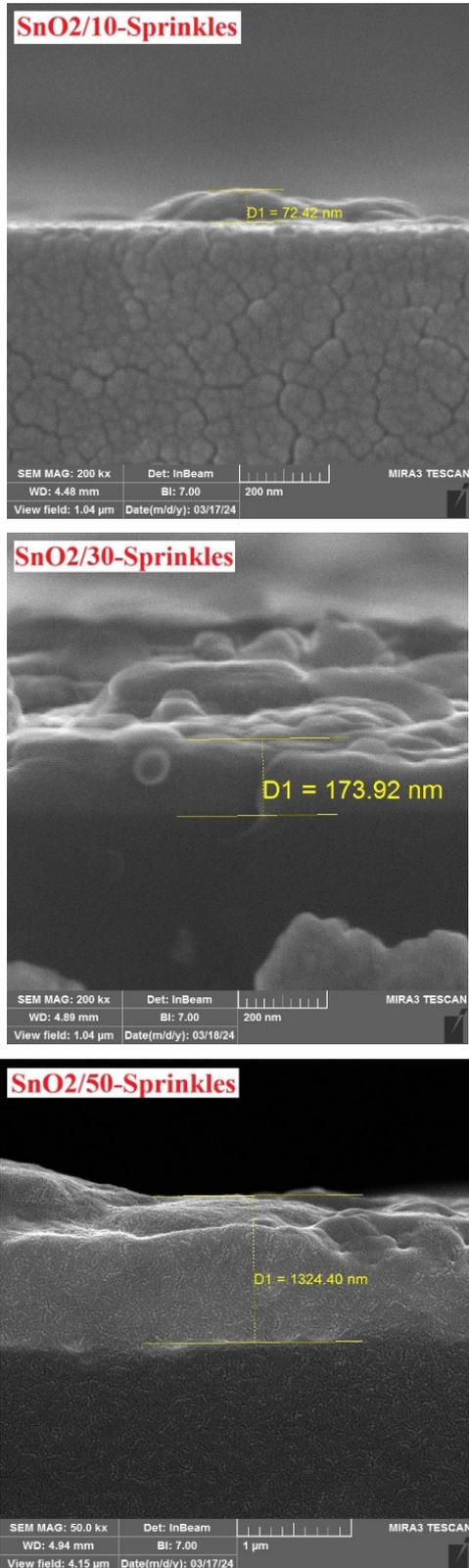


Figure 3: Cross-sectional FESEM image for SnO₂ films at different Sprinkles.

4. Optical properties

Optical absorbance is a critical factor in the operation of many optoelectronic devices, such as solar cells and photodetectors. Figure 4 shows the absorbance spectra, absorption coefficient, and optical energy gap of tin dioxide thin films at many layers (10, 30, and 50). The absorbency level exceeds when the number of sprays increases within the visual range. The curves often exhibit a high level of symmetry due to the even distribution of the film throughout the substrate. The increase in absorbance due to increased film thickness occurs when film thickness levels increase [25].

In Figure 4, the connection was used to elongate the curve between $(h\nu)$ and $(\alpha h\nu)^2$ to calculate the optical energy gap of the tin dioxide layer.

$$\alpha h\nu = A(h\nu - E_g)^{1/2} \text{-----}(2)$$

The absorption coefficient is represented by the symbol (α) , whereas (A) is a fixed numerical value. Using the Tauc formula, we determined the optical band gap values of S1, S2, and S3 to be 3.93, 3.90, and 3.83 eV, respectively. Consistent with prior research, our

investigation produced similar findings [18], [19]. The samples exhibit a reduced optical energy gap in comparison to tin dioxide [26]. The improvement of the photocatalytic efficiency of these samples can mostly be attributed to the reduction of the energy gap at

increasing crystalline levels. Materials with a limited range of energy levels between the valence and conduction bands are well suited to act as visible light photocatalysts since they can effectively absorb light at longer wavelengths [27].

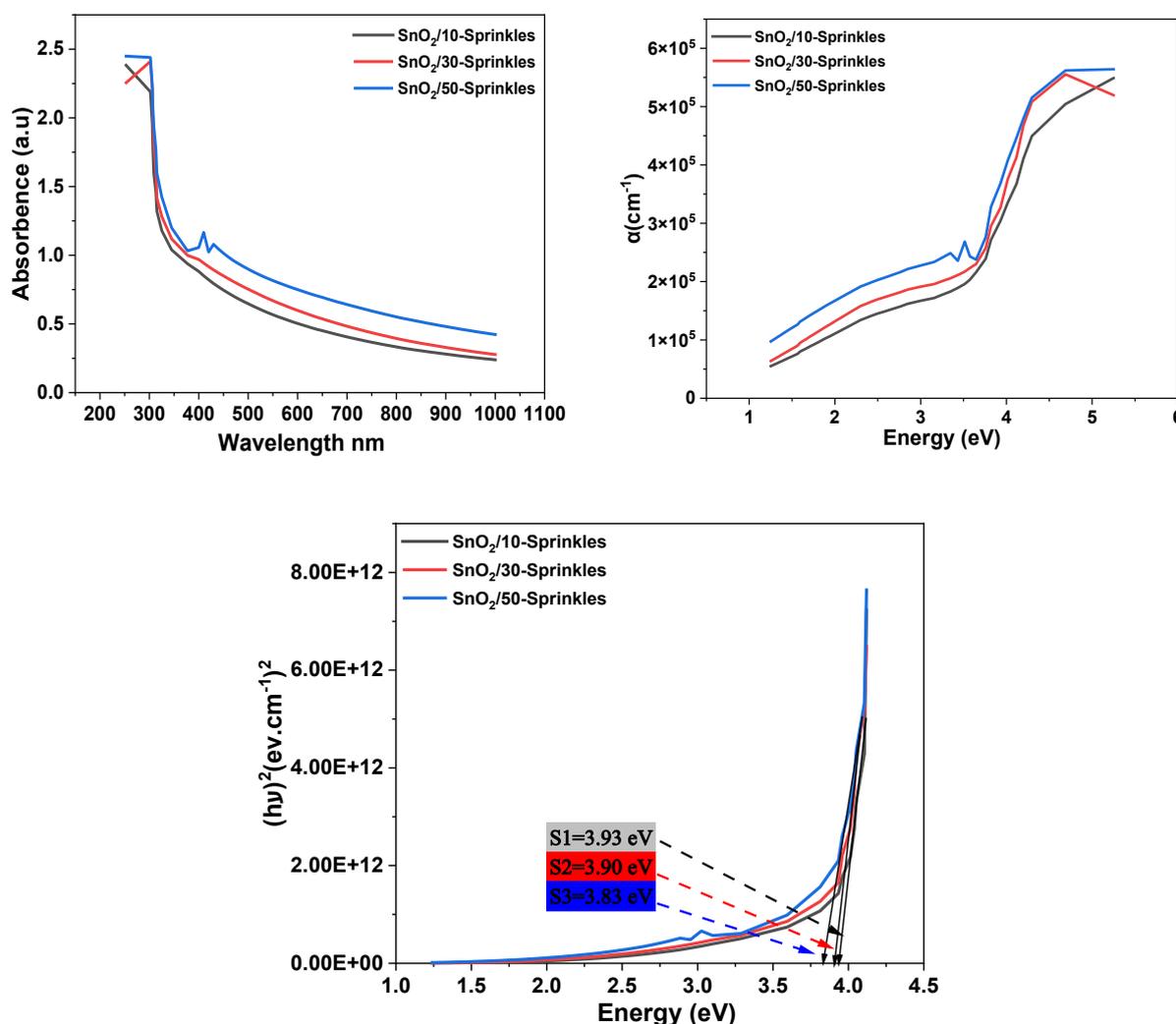


Figure 4: Absorbance, absorption coefficient, and optical energy gap of SnO₂ films at S1: (10-Sprinkles), S2: (30-Sprinkles), and S3: (50-Sprinkles).

5. Current-voltage characteristics

The IV property is essential for many interferometric techniques. Measurements of electrical properties were performed on tin dioxide coatings on glass substrates for different number of layers (10, 30, 50) sprays under light and dark conditions. We accomplished this by regularly adjusting the direct current (DC) voltage, ranging from +1V to -1V. The film surface was illuminated using a Philips halogen lamp with a power density of 104.986 mW/cm², at a distance of 20 cm. The input and output were connected by placing aluminum electrodes on the film surface. Voltage and current were measured with a Keithley 2400C. Figure 5 shows the characteristics of the relationship between current and voltage under limited lighting conditions. Recombination currents occur in the high voltage region, which is characterized by a high abundance of minority and majority carriers and a low internal carrier concentration. The majority-carrying dark current is pushed forward by the recombination current. The samples show a slight increase in recombination current within the low

voltage range. The transition from the valence band to the conduction band is a plausible explanation and is supported by a viable hypothesis. Due to the overwhelming effect of diffusion current, the current shows exponential growth with increasing voltage. The I-V characteristics of samples S1 and S2 show almost linear and symmetric behavior, indicating the presence of ohmic or subohmic conductors. [28]. This phenomenon arises when aluminum infiltrates the oxide nanostructure, facilitating the movement of electrons through the oxide rather than through the nanostructure itself. All manufactured devices exhibit Schottky behavior in film contact. The graphs show a direct relationship between current voltage and forward bias. The current increased due to the separation of electron-hole pairs and enlargement of the depletion region due to higher reverse bias voltage. Light photons generate an unintended photocurrent. As a result, there is an increasing number of light-generated charge carriers in both the diffusion carrier region and the depletion carrier region [29]. The ability of the device to generate charge carriers in response to light, even in small

amounts, is verified by the slight increase in current observed when it is illuminated [30].

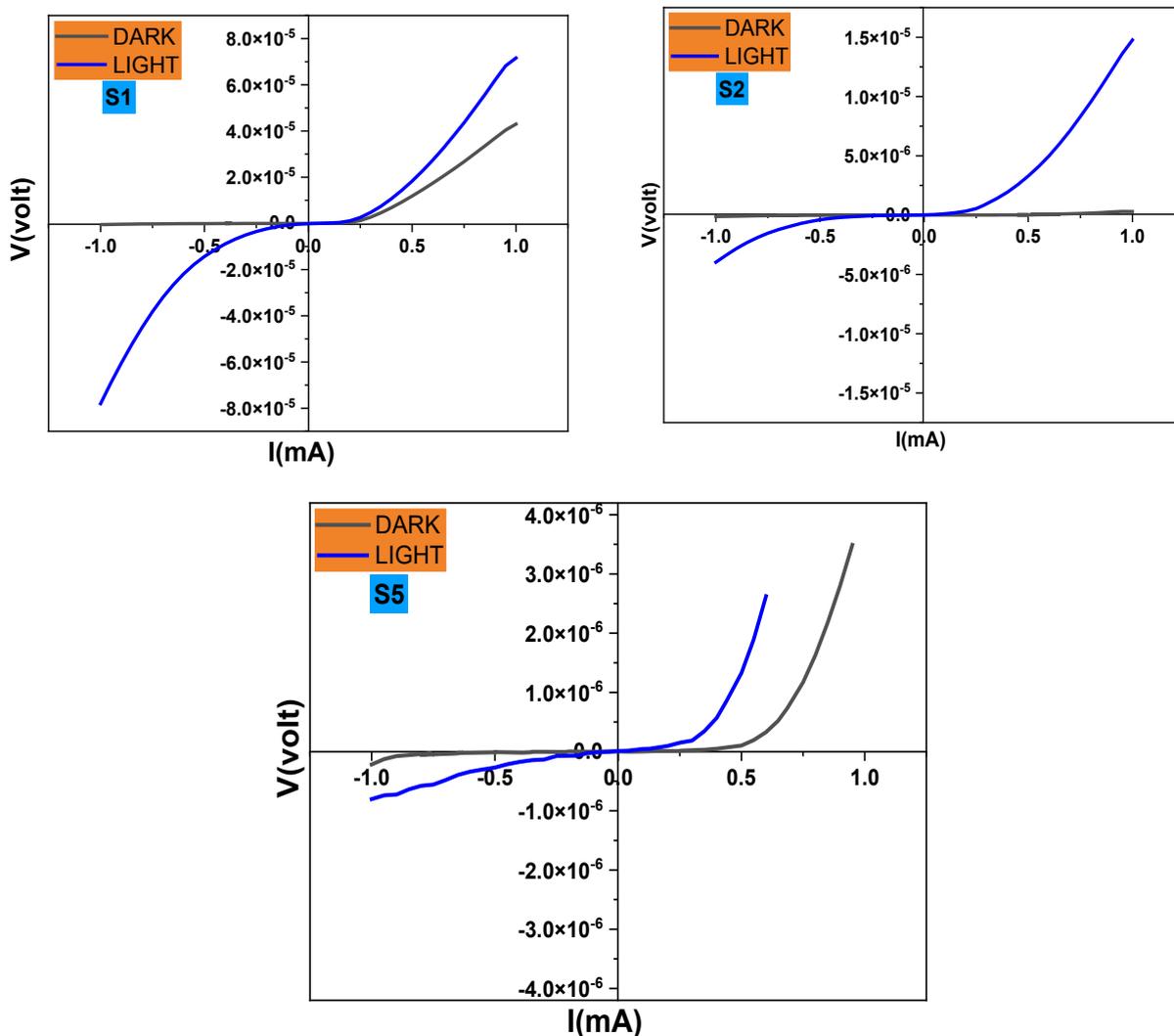


Figure 5: I-V characteristics of the SnO₂ films at S1: (10-Sprinkles), S2: (30-Sprinkles), and S3: (50-Sprinkles).

Conclusion

The films underwent hydrothermal treatment to produce nanostructured thin sheets of SnO₂. XRD measurements demonstrated the feasibility of

manipulating the crystal size by increasing the number of layers. The morphology of the nanoparticles showed variations according to increases in layer number levels, as demonstrated by

images obtained using field emission scanning electron microscopy (FE-SEM). SnO₂ thin films showed greater absorption of visible light at the levels of layers with higher thickness. S1, S2, and S3 are measured to have optical energy gaps of 3.93, 3.90, and 3.83 eV, respectively. The current and voltage are achieved and there is an improvement in the electrical properties when the light is incident.

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